



國家同步輻射研究中心
National Synchrotron Radiation Research Center

Photoemission (I) Spectroscopy

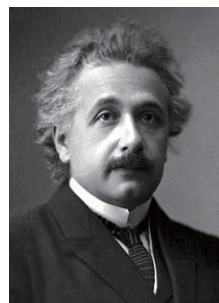
Cheiron School 2012

October 2, 2012 SPring-8, Japan

Ku-Ding Tsuei

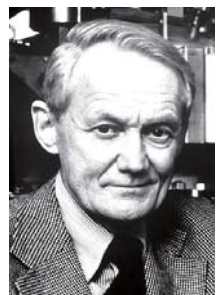
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National Synchrotron Radiation Research Center



In 1905 Albert Einstein proposed the concept of light quanta (**photons**) to explain the **photoelectric effect**, which was pivotal in establishing the **quantum theory** in physics

In 1921 he was awarded the **Nobel Prize in Physics** "for his services to theoretical physics, and especially for his **discovery of the law of the photoelectric effect**"



Since the late 1940's Kai Siegbahn has been working on the **Electron Spectroscopy for Chemical Analysis (ESCA)** also termed the X-ray Photoelectron Spectroscopy (**XPS**)

In 1981 he was awarded the **Nobel Prize in Physics** "for his contribution to the development of **high-resolution electron spectroscopy**"

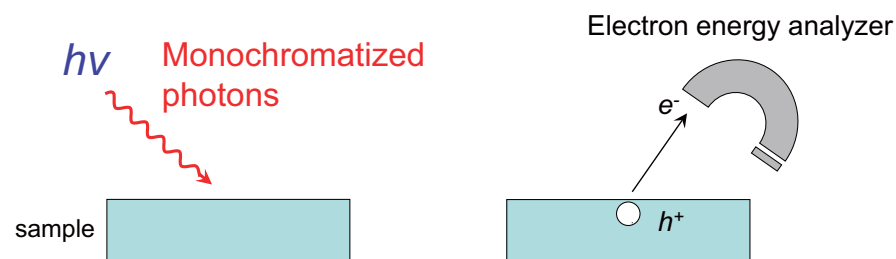
Outline

1. What is photoemission spectroscopy?
2. Fundamental aspects of photoemission.
3. Examples.
4. Increase bulk sensitivity: HAXPES.
5. Challenging future directions.

Reference books:

1. "Photoelectron Spectroscopy" 3rd Ed. by S. Hufner, Springer-Verlag 2003
2. "Angle-Resolved Photoemission: Theory and Current Applications", S. D. Kevan, ed., Amsterdam; Elsevier 1992
3. "Very High Resolution Photoelectron Spectroscopy" Ed. by S. Hufner, Springer 2007

What is photoemission spectroscopy? (photoelectron spectroscopy) (PES)



Initial state: ground (neutral) state

Final state: hole (excited) state

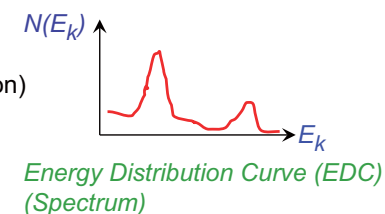
Conservation of energy

$$E_k = hv + E_i - E_f \quad (\text{most general expression})$$

E_k : photoelectron kinetic energy

$E_i(N)$: total initial state system energy

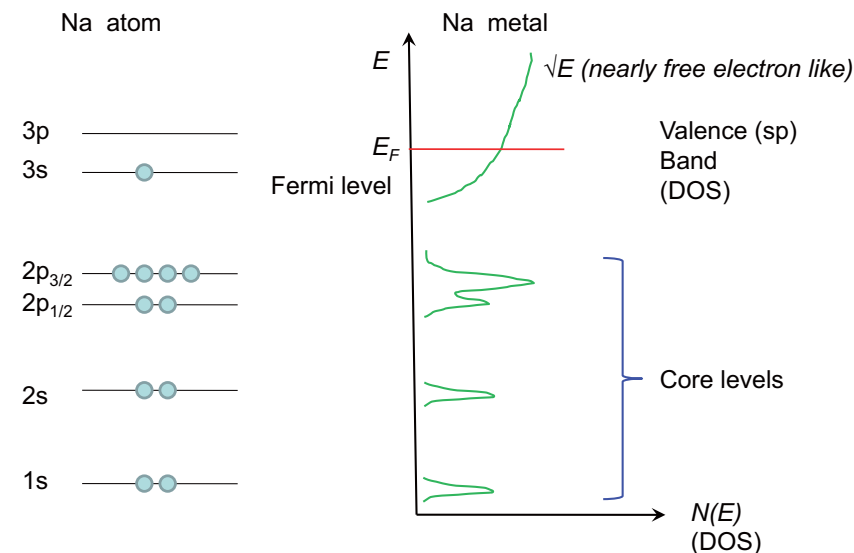
$E_f(N-1)$: total final state system energy



What are the samples and probed states?

Atoms	atomic orbitals (states)
Molecules	molecular orbitals
	core level states (atomic like)
Nanoparticles	valence bands/states
	core level states (atomic like)
Solids	valence bands
	core level states (atomic like)

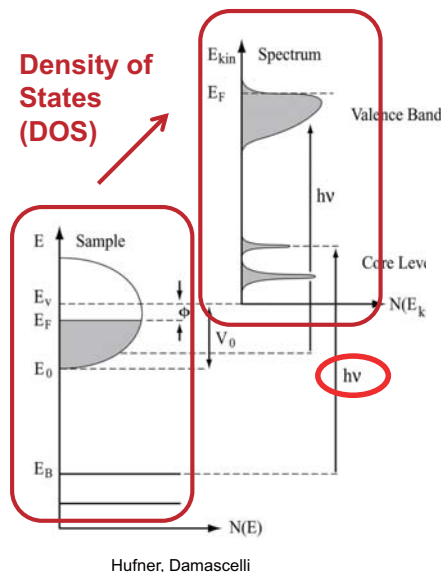
Single particle description of energy levels (Density of States) (most convenient in PE)



Energetics in PES

Conservation of energy

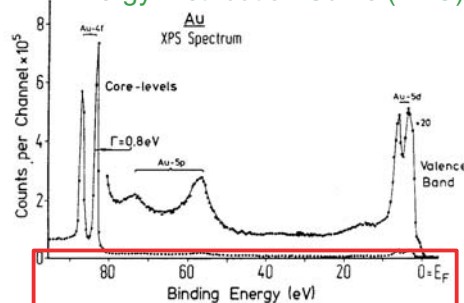
Density of States (DOS)



$$E_k = h\nu - E_B - \phi$$

E_v : vacuum (energy) level
 E_F : Fermi (energy) level
 $\phi = E_v - E_F$: work function
 E_0 : bottom of valence band
 $V_0 = E_v - E_0$: inner potential
 E_k^{max} marks E_F in spectra
 E_B measured relative to $E_F = 0$

Energy Distribution Curve (EDC)



Light sources and terminology

Ultraviolet Photoemission Spectroscopy (UPS)

UV He lamp (21.2 eV, 40.8 eV)
 valence band PE, direct electronic state info

X-ray Photoemission Spectroscopy (XPS) (Electron Spectroscopy for Chemical Analysis) (ESCA)

x-ray gun (Al: 1486.6 eV, Mg: 1253.6 eV)
 core level PE, indirect electronic state info
 chemical analysis

Synchrotron radiation:

continuous tunable wavelength
 valence band: <100 eV, maybe up to several keV
 core level: 80-1000 eV, maybe up to several keV
 depending on core level binding energies

Inelastic Electron Mean Free Path (IMFP)

$$I(d) = I_0 e^{-d/\lambda(E)}$$

$\lambda(E)$: IMFP depending on KINETIC ENERGY inside solid or relative to E_F

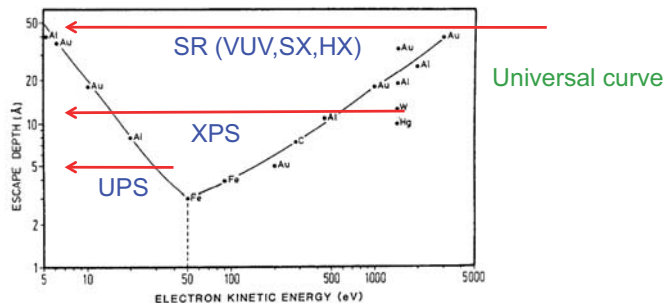


Fig.1.9. Electron escape depth as a function of their kinetic energy for various metals. The data indicate a universal curve with a minimum of 2-5 Å for kinetic energies of 50-100 eV. The scatter of the data is evident from the values obtained at $E_{kin} = 1480$ eV

Hufner

Minimum due to electron-electron scattering, mainly plasmons

PE is a surface sensitive technique! (requires UHV)

High energy photoemission: several keV to increase bulk sensitivity

Table 1-1. Electron binding energies, in electron volts, for the elements in their natural forms.

Element	K Is	L ₁ 2s	L ₂ 2p _{3/2}	L ₃ 2p _{1/2}	M ₁ 3s	M ₂ 3p _{3/2}	M ₃ 3p _{1/2}	M ₄ 3d _{5/2}	M ₅ 3d _{3/2}	N ₁ 4s	N ₂ 4p _{3/2}	N ₃ 4p _{1/2}
1 H	13.6											
2 He	24.6											
3 Li	54.7											
4 Be	111.5											
5 B	188*											
6 C	284.2*											
7 N	409.9*	37.3*										
8 O	543.1*	41.6*										
9 F	686.7*											
10 Ne	870.2*	48.8*	21.7*	21.6*								
11 Na	1070.8*	63.5*	30.6*	30.81								
12 Mg	1303.0*	88.7	40.76	40.50								
13 Al	1584.6	117.8	72.65	72.55								
14 Si	1839	140.7*	99.82	99.42								
15 P	2344.5	139*	138*	139*								
16 S	2472	230.9	163.6*	162.5*								
17 Cl	2822.4	270*	202*	200*								
18 Ar	3205.9*	326.3*	250.6*	248.4*	29.3*	15.9*	15.7*					
19 K	3608.4*	376.6*	297.3*	294.6*	34.8*	18.3*	18.3*					
20 Ca	4038.5*	434.4*	349.7*	346.2*	44.3*	23.4*	23.4*					
21 Sc	5465	426.7*	519.8*	512.1*	66.3*	37.2*	37.2*					
22 Ti	5999	496.0*	593.8*	574.1*	74.1*	42.2*	42.2*					
23 V	6539	560.1*	644.9*	636.7*	82.3*	47.2*	47.2*					
24 Cr	7112	644.6*	718.9*	706.8*	91.3*	52.7*	52.7*					
25 Mn	7700	725.1*	793.2*	778.1*	101.0*	58.9*	59.9*					
26 Fe	8333	1008.6*	870.0*	852.7*	110.8*	68.0*	66.2*					
27 Co	8970	1096.7*	952.3*	932.7*	122.5*	77.3*	75.1*					
28 Ni	9589	1196.2*	1044.9*	1023.8*	139.8*	91.4*	88.6*	192*	10.4*			
29 Cu	10567	1290.9*	1143.2*	1116.4*	158.5*	103.5*	100.0*	18.7*	18.7*			
30 Zn	11103	1414.6*	1240.1*	1217.0*	180.1*	124.9*	120.8*	29.8	29.2			
31 Ga	11867	1527.0*	1359.1*	1323.6*	204.7*	146.2*	141.2*	41.7*	41.7*			
32 Ge	12658	1652.0*	1474.3*	1433.9*	229.6*	166.5*	160.7*	55.9*	54.6*			
33 As	13474	1782*	1596*	1550*	257*	189*	182*	70*	69*			
34 Se	14326	1921	1730*	1676.4*	292.3*	222.2*	214.4	95.0*	95.0*	27.5*	14.1*	14.1*
35 Br	15200	2067	1884	1826.7*	326.7*	248.7*	239.1*	113.0*	112*	30.7*	16.3*	15.3*
36 Kr	16105	2216	2067	1999	358.7*	280.3*	270.0*	134.0*	134.2*	38.9*	21.3	20.1*
37 Rb	17038	2373	2156	2080	392.0*	310.6*	298.8*	157.7*	155.8*	43.8*	24.4*	23.1*
38 Sr	17998	2532	2307	2223	430.3*	343.5*	329.8*	181.1*	178.8*	50.6*	28.5*	27.1*
39 Y	18986	2698	2465	2373	466.6*	376.1*	360.6*	205.0*	202.3*	56.4*	32.6*	30.8*
40 Zr	20000	2866	2625	2529	506.3*	411.6*	394.0*	231.1*	227.9*	63.2*	37.6*	35.5*
41 Nb	21084	3041	2793	2677	544*	447.6	417.7	257.6	255.9*	69.9*	42.3*	39.9*
42 Mo	22117	3224	2967	2838	586.1*	483.5*	463.4*	284.2*	280.0*	75.0*	46.3*	43.2*
43 Tc	23220	3412	3146	3004	628.1*	521.3*	496.5*	311.9*	307.2*	81.4*	50.5*	47.3*
44 Ru	24350	3604	3330	3173	671.6*	559.0*	532.3*	340.5*	335.2*	87.1*	55.7*	50.9*
45 Rh	25514	3806	3524	3351	719.0*	603.8*	573.0*	374.0*	368.3	97.0*	63.7*	58.3*

Core level binding energies are characteristic of each orbital of each element

Finger prints

Core level BE independent of photon energy used

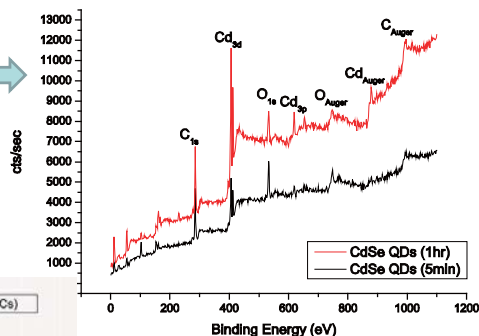
X-Ray Data Booklet

<http://xdb.lbl.gov/>

Core level photoemission: chemical analysis of elements

ESCA (XPS)

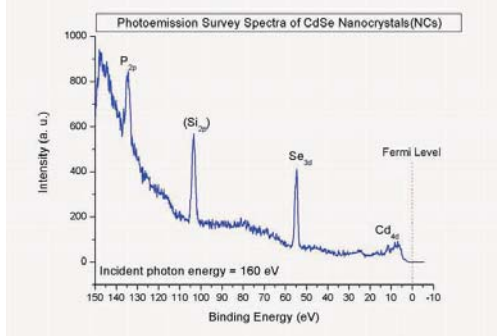
$h\nu = \text{Mg } K\alpha = 1253.6 \text{ eV}$



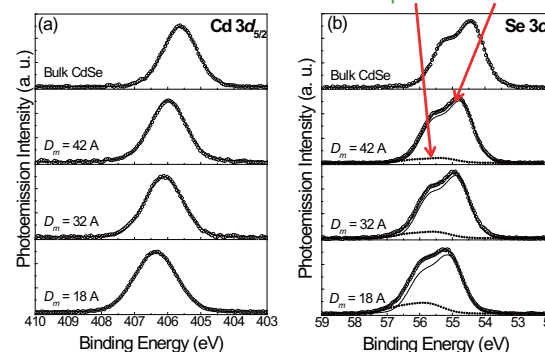
Different photon energy \rightarrow different relative cross section for various core levels \rightarrow Relative intensity changes with photon energy

PJW, NSRRC

Synchrotron $h\nu = 160 \text{ eV}$

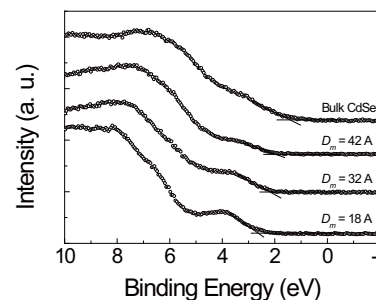


surface component bulk component



Surface core level shift (chemical and/or environmental)

A case study of IMFP applied to PE of CdSe nano particles with tunable SR
How to choose photon energies for valence and different core levels with the max surface sensitivity?



Actual choices:

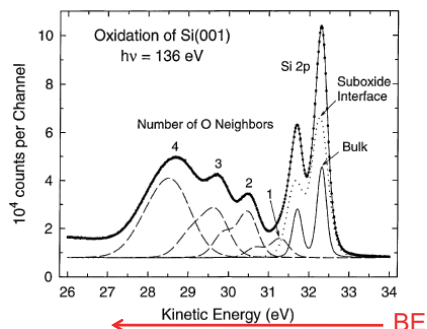
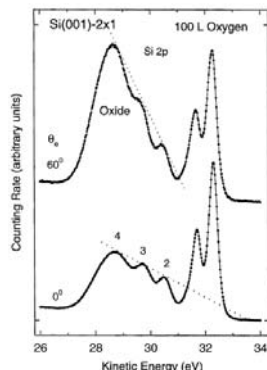
Cd 3d_{5/2}: 480 eV
Se 3d: 120 eV
Valence band: 50 eV

$E_k \sim 45-74 \text{ eV}$, most surface sensitive

Wu, PRB 2007 NSRRC

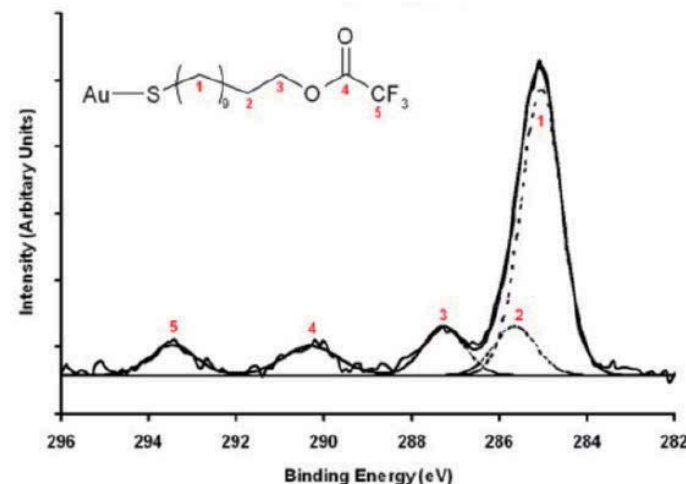
Core level photoemission: chemical shift

higher oxidation state
=> higher BE



higher emission angle
→ more surface sensitive
(IMFP) Pi, SS 2001 NSRRC

Chemical Analysis of C1s core levels



<http://surfaceanalysis.group.shef.ac.uk>

Auger Electron Spectroscopy

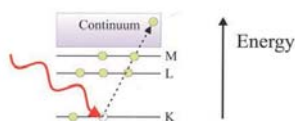
Core electron ionized by
photons or high energy
electrons
Non-radiative core hole decay
→ Auger electron emission
Radiative decay
→ Fluorescent x-ray emission

Comparison between PES
and AES

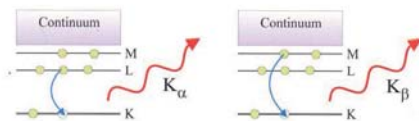
PES: constant BE, E_k shift
with changing photon energy
AES: constant E_k , apparent
BE shift with changing photon
energy
(synchrotron)

<http://xdb.lbl.gov/>
[Handbook of XPS](#)

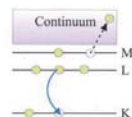
(a) Photoelectric absorption



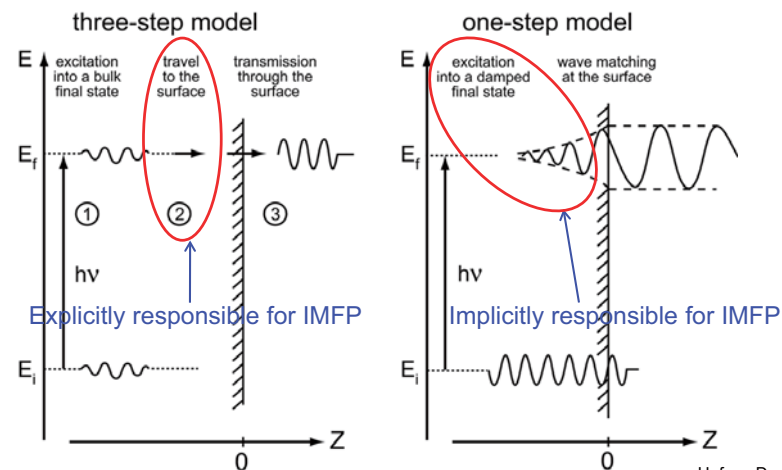
(b) Fluorescent X-ray emission



(c) Auger electron emission



Photoemission Process

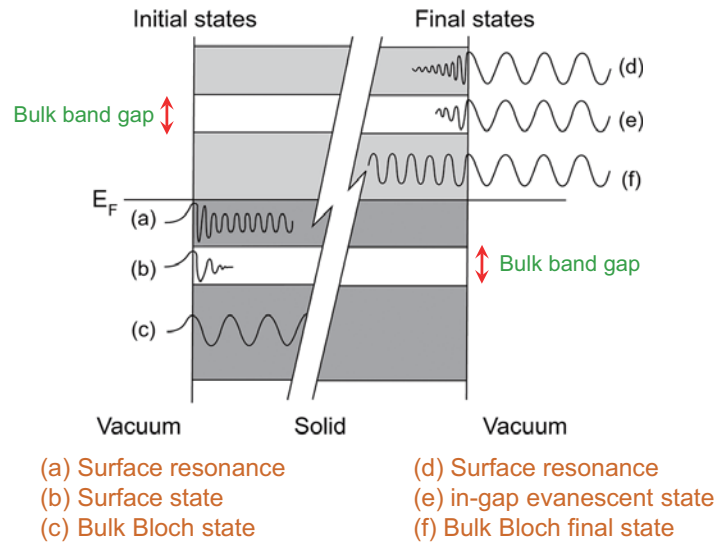


Conceptually intuitive,
Simple calculation works

Rigorous,
requires sophisticated calculation

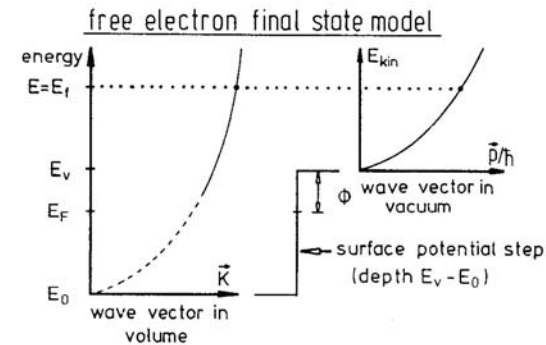
Hufner, Damascelli

Schematic wave functions of initial and final states (valence band initial states)



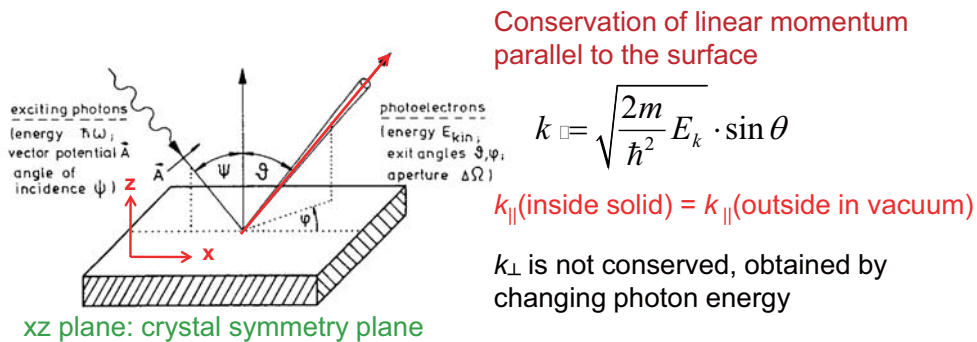
Electron kinetic energy inside and outside of solids

Inner potential: $E_V - E_0$



Concept of inner potential is used to deduce 3D band structure from PE data assuming free electron like final state inside solids

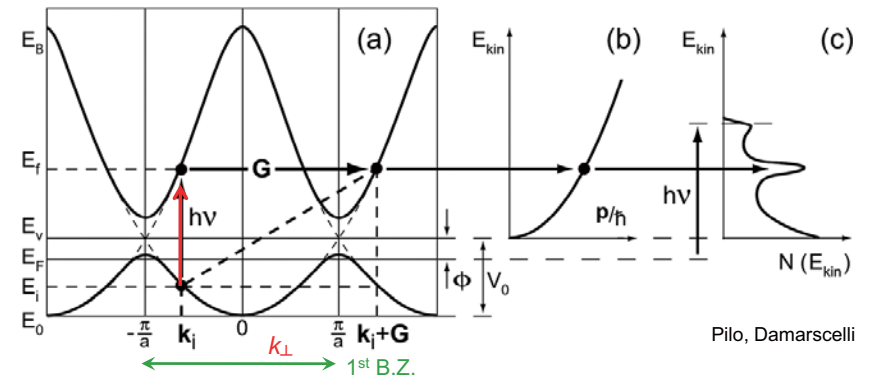
Angle-resolved photoemission (ARPES)



Electron emission angle θ with respect to the crystalline surface normal and symmetry planes is also measured

⇒ Electronic band dispersion $E(k_{\parallel}, k_{\perp})$
inside (ordered) crystalline solids

Band Mapping (3D) $E(k_{\perp}, k_{\parallel}=0)$



Vertical transition (using visible, uv and soft x-rays) at normal emission

For hard x-ray photon momentum cannot be neglected

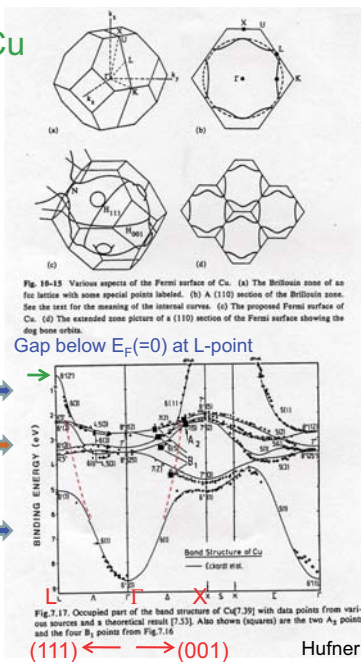
Using different $h\nu$ at normal emission to map out $E(k_{\perp})$

Bulk band structure and Fermi surfaces

Fermi surfaces:

Electron pockets and hole pockets
Related to
Hall coefficient
Electric conductivity
Magnetic susceptibility

Cu



(nearly free electron like) sp -band

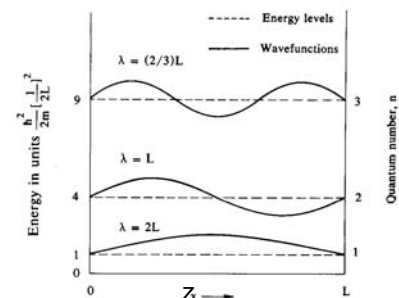
Small dispersion d -band
more localized state

Large dispersion sp -band
extended state

Dispersion of a band can tell how localized
or extended a state is in a solid

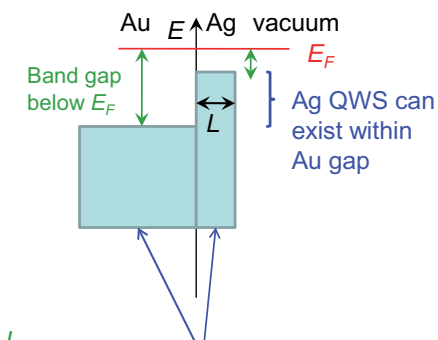
Quantum well states: manifestation of particle in a box in real materials

Ag(111) thin films epitaxially
grown on Au(111) substrate



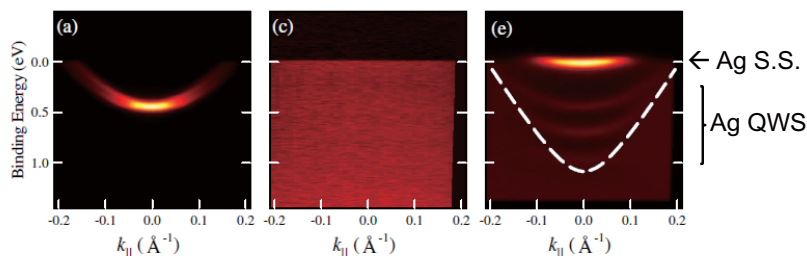
Quantized discretely along z -direction
Energy levels depend on film thickness L

Nearly free electron like in xy -plane

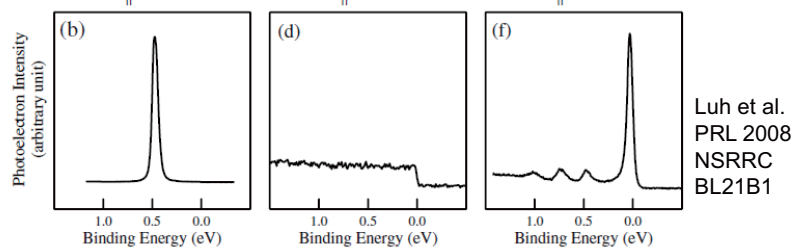


Bulk projected bands along ΓL
of Au and Ag, respectively

2D
Int.
plots



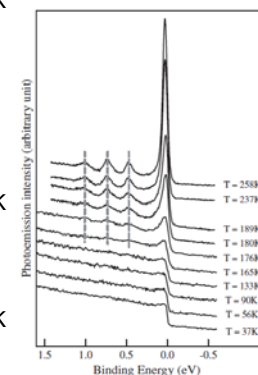
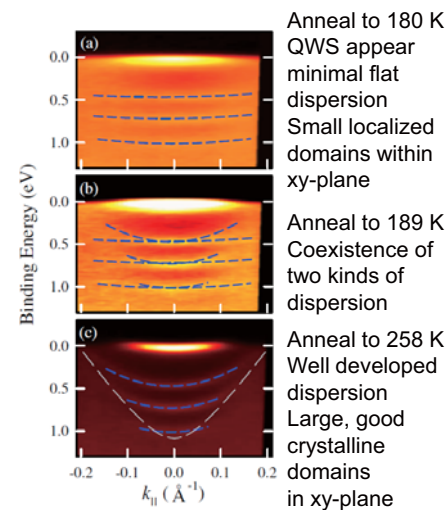
$k_{||} = 0$
EDCs



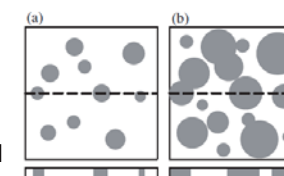
Clean Au(111)
surface state

Deposit 22 ML Ag
at 37 K
disordered form

Anneal to 258 K
Atomically flat
22 ML thin film



Same QWS energies \rightarrow
Same crystalline film
thickness along z
even though lateral
crystalline domains
grow from small to
large



Proposed growth model

Annealing Temp \rightarrow

One-particle spectral function near E_F measured by ARPES with many-particle correction (quasi-particle)

$$A(k, \omega) = -\frac{1}{\pi} \frac{\Sigma''(k, \omega)}{[\omega - \varepsilon_k - \Sigma'(k, \omega)]^2 + [\Sigma''(k, \omega)]^2}$$

ε_k : single particle energy without many-particle correction

$\omega = 0 : E_F$

Self energy correction due to interaction with phonons, plasmons and electrons, etc.

$$\Sigma(k, \omega) = \Sigma'(k, \omega) + i\Sigma''(k, \omega)$$

Real part: shift observed peak energy from single particle energy

Imaginary part: peak FWHM = $2 \Sigma''$

ARPES for valence band PE uses primarily VUV light because of

1. Better absolute photon energy resolution for most BLs designed as nearly const $\Delta E/E$.

2. Better photoionization cross section at low photon energy.

3. Better momentum resolution for a given angular resolution.

$$\Delta k_{\parallel} (1/\text{\AA}) = 0.5123 \sqrt{(E_k(\text{eV})) \cos(\theta)} \Delta \theta$$

SX ARPES has been tried for increasing bulk sensitivity, more free electron like final states and reduced matrix element effects. The increasing bulk sensitivity will be discussed.

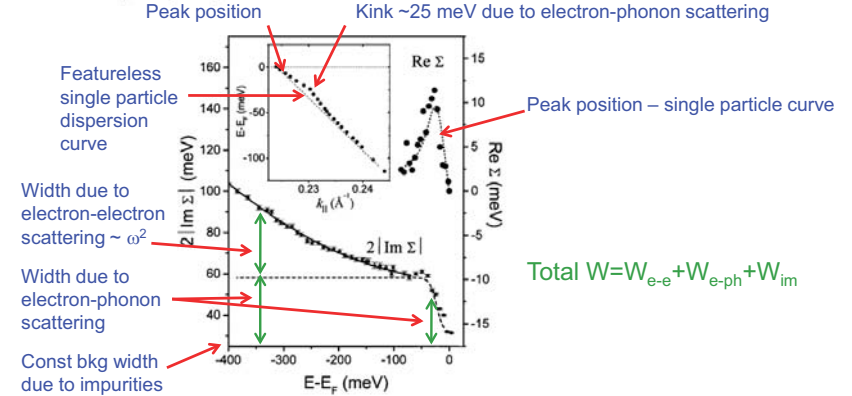
Many-Body Effects in Angle-Resolved Photoemission: Quasiparticle Energy and Lifetime of a Mo(110) Surface State

T. Valla,¹ A. V. Fedorov,¹ P. D. Johnson,¹ and S. L. Hulbert²

¹Department of Physics, Brookhaven National Laboratory, Upton, New York 11973-5000

²National Synchrotron Light Source, Brookhaven National Laboratory, Upton, New York 11973-5000
(Received 28 January 1999)

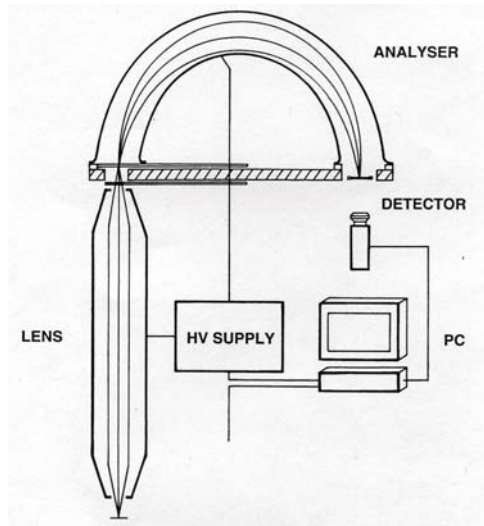
In a high-resolution photoemission study of a Mo(110) surface state various contributions to the measured width and energy of the quasiparticle peak are investigated. Electron-phonon coupling, electron-electron interactions, and scattering from defects are all identified mechanisms responsible for the finite lifetime of a valence photohole. The electron-phonon induced mass enhancement and rapid change of the photohole lifetime near the Fermi level are observed for the first time.



NSRRC U9 BL21B1 BL and high resolution photoemission end station



Hemispherical electron energy analyzer



$R1$: radius of inner sphere
 $R2$: radius of outer sphere
 $R_o = (R1 + R2) / 2$: mean radius
 and along electron path
 $V1$: inner potential
 $V2$: outer potential
 E_p : pass energy = electron kinetic energy along mean radius

Comments on photoelectron IMFP

Valence band PE using VUV and SX has IMFP near minimum, very surface sensitive. It is great to probe surface electronic structure such as surface states and surface resonances.

Many **strongly correlated systems** have electronic structure sensitive to coordination, thus **surface contains different electronic structure from that of deeper bulk**. Great surface sensitivity posts a serious problem to probe true bulk properties.

Buried interface is mostly undetectable by PE using VUV/SX photons because IMFP is too small compared to thickness of outermost thin layer.

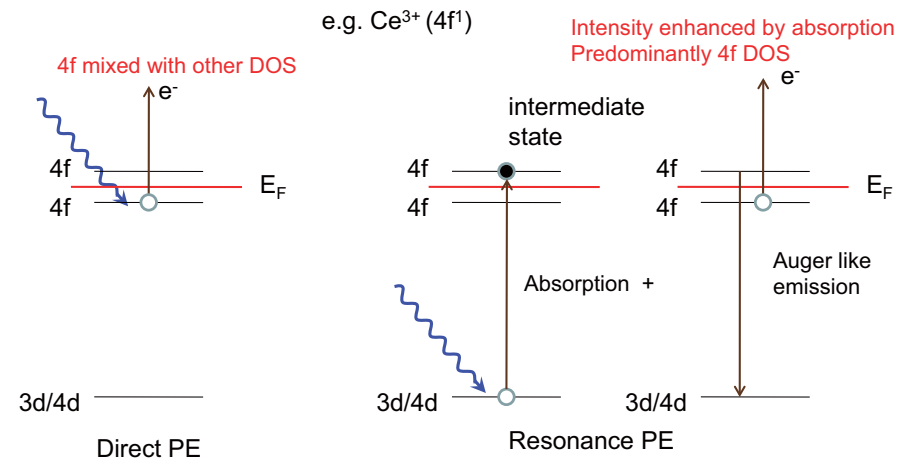
Need larger IMFP by using higher energy photons to enhance bulk sensitivity.

Drive to go to even higher photon energies into hard x-ray regime

HARD X-ray PhotoEmission Spectroscopy (HAXPES)

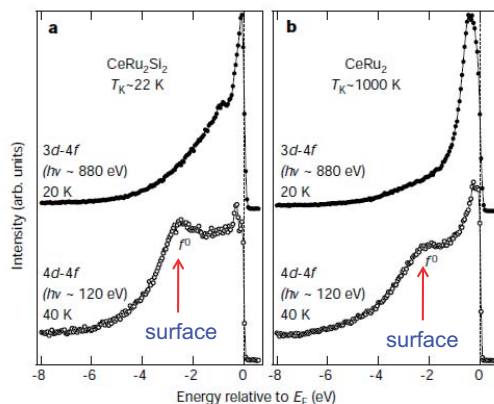
HAXPES not only reach even closer to **true bulk properties** of strongly correlated systems, but also becomes capable of probing **interface electronic structure**. Very difficult using conventional VUV/SX.

Resonance photoemission (near-edge absorption followed by Auger like electron emission)



Probing bulk states of correlated electron systems by high-resolution resonance photoemission

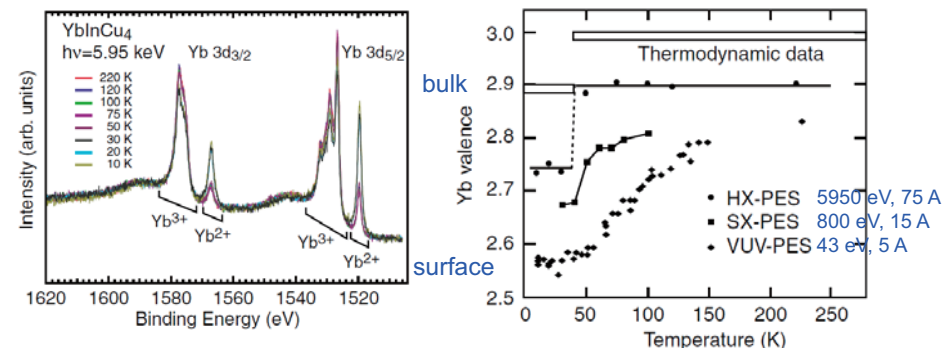
A. Sekiyama*, T. Iwasaki*, K. Matsuda*, Y. Saitoh*, V. Onuki* & S. Suga*



By using Ce 3d → 4f Res. PE near 880 eV surface 4f component becomes greatly reduced compared to 4d → 4f Res. PE near 120 eV, the resulting spectra are closer to true bulk 4f DOS.

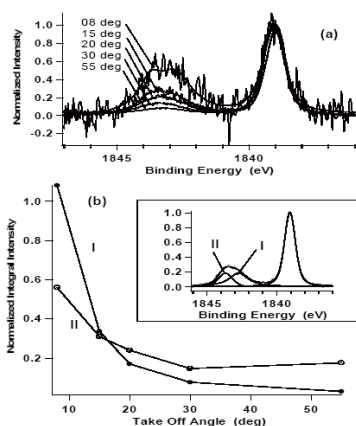
Valence Transition of YbInCu₄ Observed in Hard X-Ray Photoemission Spectra

Hitoshi Sato,^{1,*} Kenya Shimada,¹ Masashi Arita,¹ Koichi Hiraoka,² Kenichi Kojima,³ Yukiharu Takeda,^{1,†} Kunta Yoshikawa,⁴ Masahiro Sawada,¹ Masashi Nakatake,¹ Hirofumi Namatame,¹ Masaki Taniguchi,^{1,4} Yasutaka Takata,⁵ Eiji Ikenaga,⁶ Shik Shin,^{5,7} Keisuke Kobayashi,⁶ Kenji Tamasaku,⁸ Yoshinori Nishino,⁸ Daigo Miwa,⁸ Makina Yabashi,⁶ and Tetsuya Ishikawa⁸

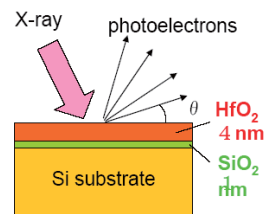


Bulk sensitive HAXPES can determine sharp first order valence band transition

HAXPES example: Hard x-ray photoemission on Si-high k insulator buried interface



Kobayashi, APL 2003 SPring-8



Annealed sample
HfSix formation

$h\nu = 6 \text{ keV}$, $\Delta E \sim 0.24 \text{ eV}$

Take-off angle dependence => non-destructive depth profile

Can probe buried interface at 35 nm ! (achievable only by hard x-ray PE)

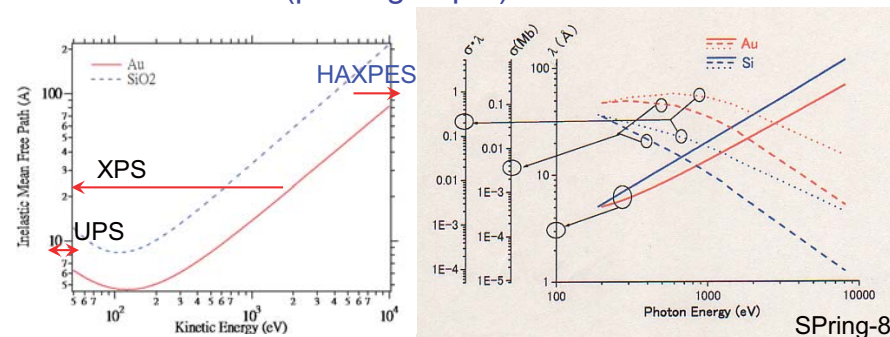
NSRRC HAXPES project at SPring-8

World wide efforts on SR based HAXPES

- * **SPring-8** BL29XU (RIKEN, HAXPES end station can move in, pioneer in HAXPES)
- * **SPring-8** BL15XU (National Institute Materials Science (NIMS) WEBRAM, fixed installation)
- * **SPring-8** BL19LXU (RIKEN long undulator BL, HAXPES end station can move in)
- * **SPring-8** BL46XU (JASRI Engineering Science Research, fixed installation)
- * **SPring-8** BL47XU (JASRI HXPES, fixed installation)
- * **SPring-8 BL12XU-SL (NSRRC, fixed installation) unique with dual analyzers**
- * **ESRF** ID16 (mainly for IXS, used by VOLPE)
- * **ESRF** ID32 (fixed installation, shared with XRD)
- * **ESRF** BM32 SpLine (fixed installation, PXD/XAS/SRD/HAXPES+SXRD)
- * **BESSY II** KMC-1 BM (HIKE and XUV diffraction, fixed installation)
- * **NLSL** X24A BM (fixed installation)
- * **DESY** BW2 Wiggler (fixed installation)
- * **DLS** I09 (Surface and Interface Analysis (SISA))
- * **SOLEIL** Galaxies (under construction, RIXS and HAXPES)
- * **CLS** SXRMB BM (wide range 1.7-10 keV)
- * **APS** (?)

Why Hard X-rays?

Electron IMFP (probing depth) and Cross section



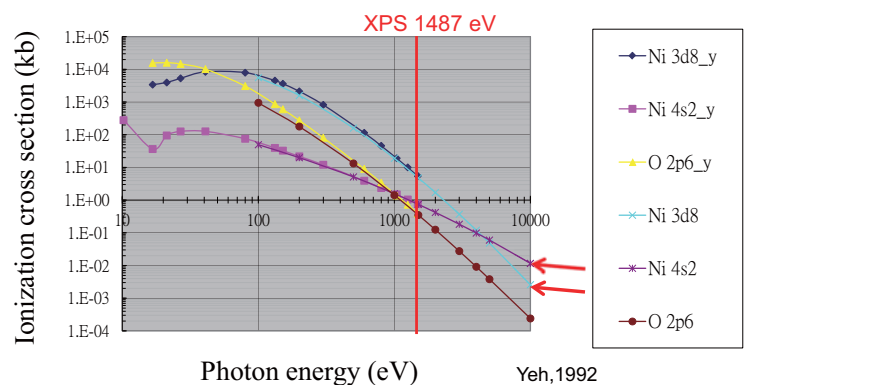
Higher E_k for deeper probing depth or more bulk sensitivity, for strongly correlated systems and interface properties

Photoemission signal ($\sigma \cdot \lambda$) decreases rapidly > 1 keV

Need photon source of higher flux/brightness (modern SR), efficient BL design and good electron analyzers

HAXPES is a low count rate, photon hungry experiment!
(except at a grazing incident angle)

A serious issue on going to hard x-rays



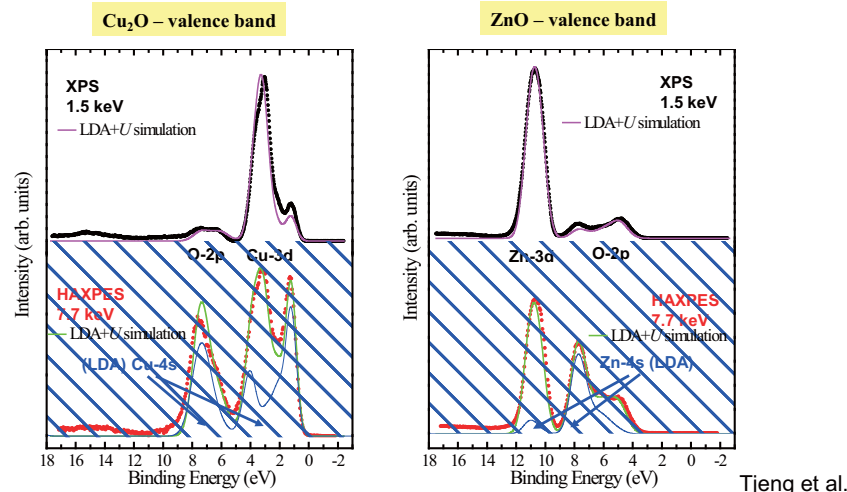
Cross sections of 3d TM s-orbitals go down more slowly than d-orbitals which are the needed information on 3d TM strongly correlated electron systems. Hard x-ray PE spectra could be dominated by contribution from less desired s-orbitals

How to cope with this problem?

Unexpected lineshapes in HAXPES compared to XPS

Valence band of simple oxides – e.g. Cu_2O and ZnO

band-insulators, no electron-correlation effects – LDA should do ($+U_{dd}+U_{pp}$)



HAXPES: TM-4s overwhelms TM-3d and O-2p

Polarization dependent cross sections in HAXPES

How to suppress the 4s spectral weight?

- photo-ionization cross-section depends on e⁻ emission direction and light polarization
- make use of β -asymmetry parameter

$$\frac{d\sigma_i}{d\Omega} = \frac{\sigma_i}{4\pi} [1 + \beta P_2(\cos \theta) + \dots]$$

β -parameters @ $h\nu = 5-10$ keV

Cu 3d 0.48 - 0.32

Cu 4s 1.985

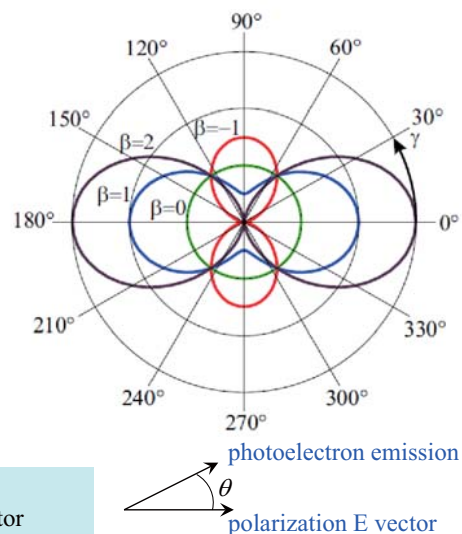
Zn 3d 0.50 - 0.33

Zn 4s 1.987 - 1.986

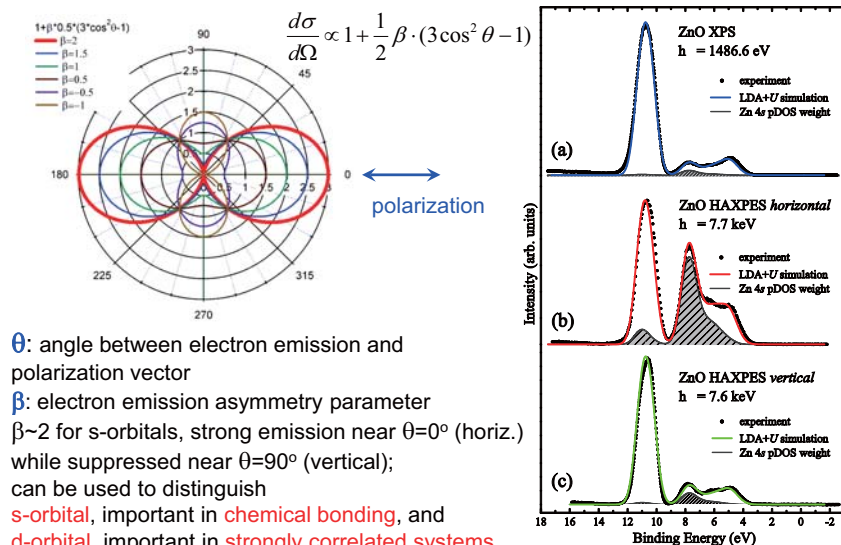
In general: s orbitals have $\beta \approx 2$:

- intensity is *enhanced* for e⁻ emission \parallel E-vector
- intensity *vanishes* for e⁻ emission \perp E-vector

→ choose suitable experimental geometry !



HAXPES Commissioning: Horizontal vs Vertical geometries



θ : angle between electron emission and polarization vector
 β : electron emission asymmetry parameter
 $\beta \sim 2$ for s-orbitals, strong emission near $\theta=0^\circ$ (horiz.) while suppressed near $\theta=90^\circ$ (vertical);
 can be used to distinguish s-orbital, important in **chemical bonding**, and d-orbital, important in **strongly correlated systems**

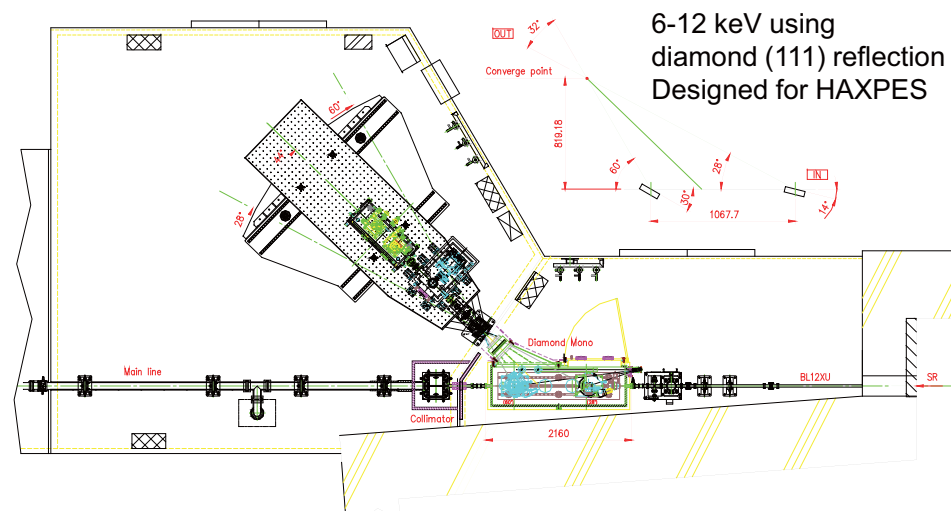
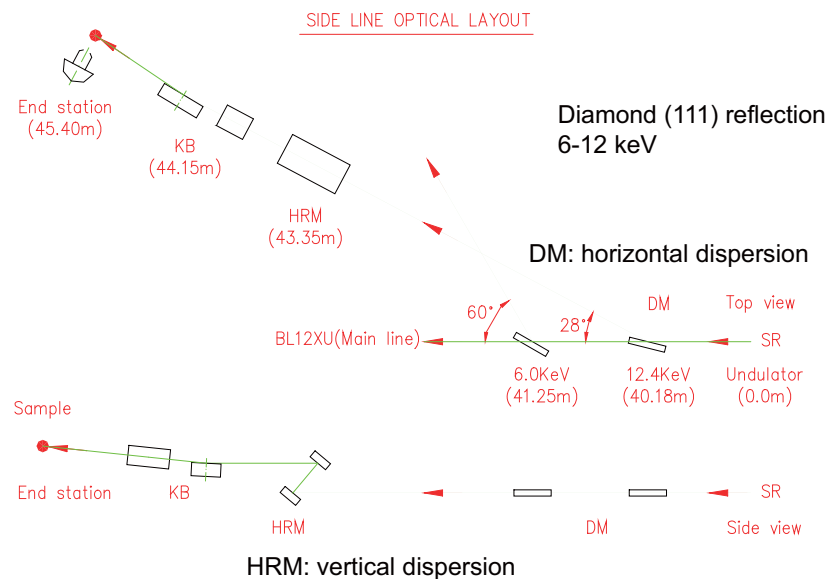
Zn 4s has relatively larger cross section than 3d at 7.6 keV compared to 1.486 keV, enhanced in horizontal geometry at 7.6 keV, while suppressed in vertical geometry

horizontal
 $\theta=0^\circ$

vertical
 $\theta=90^\circ$

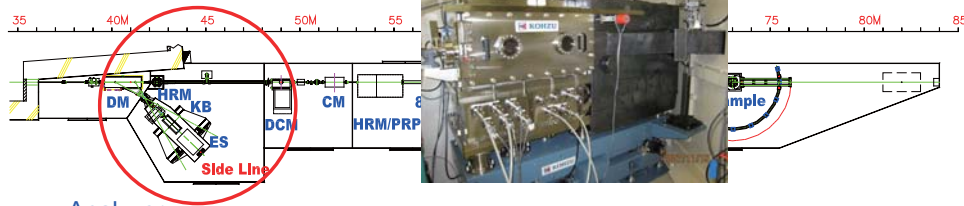
Tjeng et al.

Optical design concept



Layout of the side beamline of BL12XU

BL12XU Sideline



Analyzer



Horizontal geometry



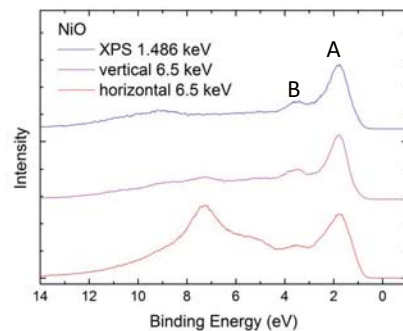
Vertical geometry

For selecting different orbital symmetries in valence band

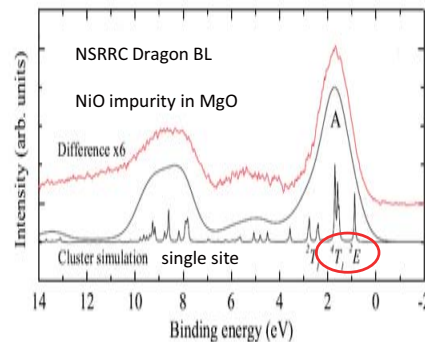
HAXPES Example 1: NiO at RT and high temp.

Interpretation of XPS valence spectra of NiO
against argument of surface effect
First ionization (photohole final) valence state
identified as Ni^{2+} low spin state
Indication of non-local screening in valence band
of bulk NiO compared to impurity NiO
Peaks splitting due to non-local screening in
valence and Ni 2p core level diminishes as
temp. approaches $T_N=523$ K

NiO: a prototypical strongly correlated electron system



Peak B is a true bulk feature



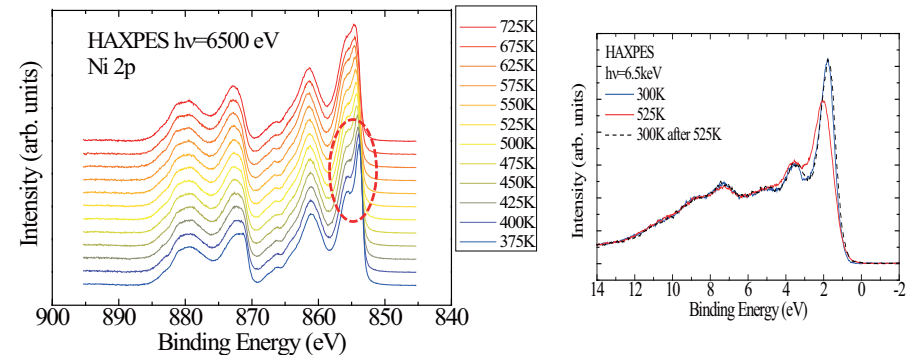
Peak B is absent in single NiO_6 cluster

Implications:

1. First ionization state is 2E (compensated spin, (photo)hole in the mixed state made of e_g (d^7) and $O\ 2p_\sigma$ (d^8L) (ZR-doublet), instead of 4T_1 (atomic-like Hund's rule high spin, d^7 , quasi-core) as previously suggested.
2. Peak B due to non-local (neighboring sites) effect.

NiO above Neel temperature at 523 K

How important is long range AF ordering?

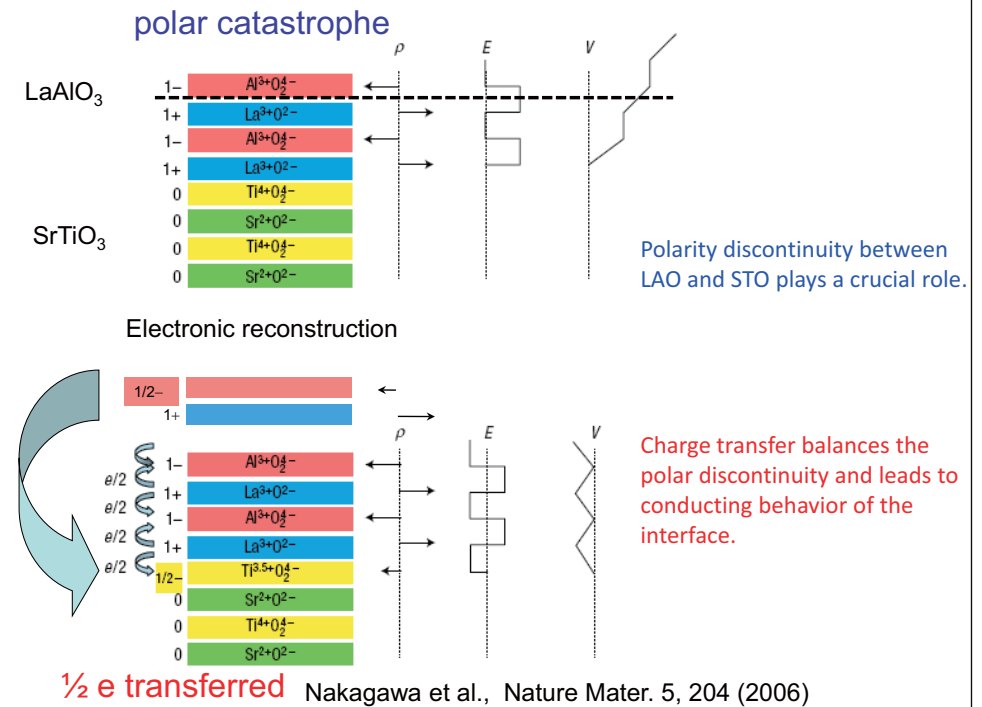


- Ni $2p_{3/2}$ splitting due to non-local screening mechanism (Veenendaal and Sawatzky PRL1993)
- Splitting goes smaller with increasing temp.
- Valence band doublet structure also changes w/ temp.

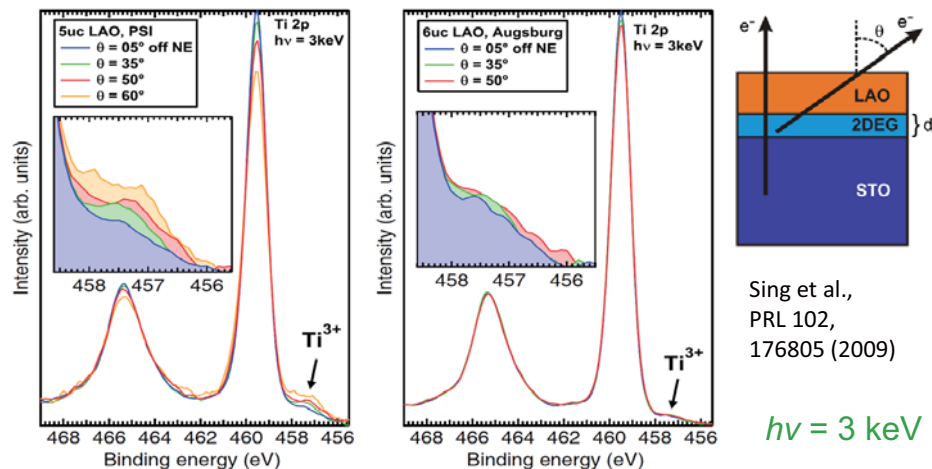
(Why need bulk sensitive HAXPES? Because O decomposes leaving surf. at high T)

HAXPES Example 2: Interface of LAO/STO

Interface of two band insulators LaAlO_3 and SrTiO_3 becomes metallic-like. Evidence of charge transfer from LAO to STO is observed but the amount is less than prediction of simplest model



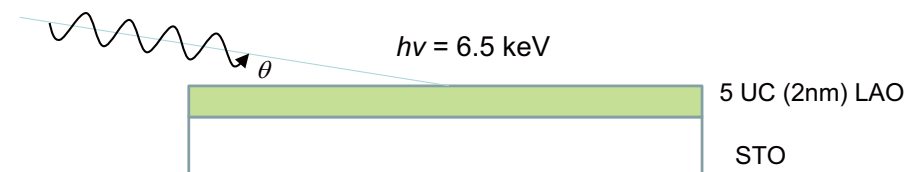
Hard X-ray Photoemission Spectroscopy (HAXPES)



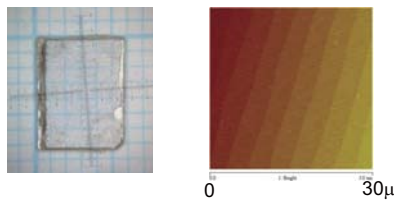
- ⇒ Conducting interface due to electronic reconstruction
- ⇒ 2DEG confined to only ~ 1 or at most a few u.c. thick
- total Ti³⁺ density < 0.28 e /2D u.c. for 5 u.c. LAO (<0.5 e); sample dependent

Our approach:

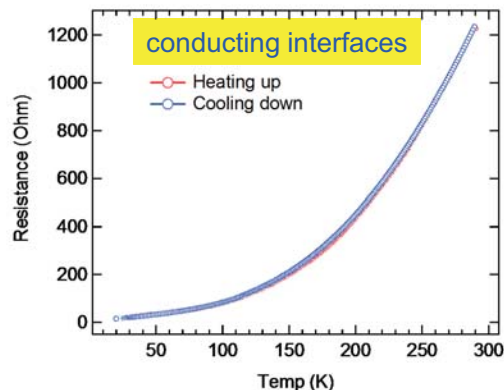
- * grazing incidence near total external reflection to enhance photon field near the surface and interface region for better detection of Ti³⁺ near the interface
- * higher photon energy (6.5 keV) to increase probing depth



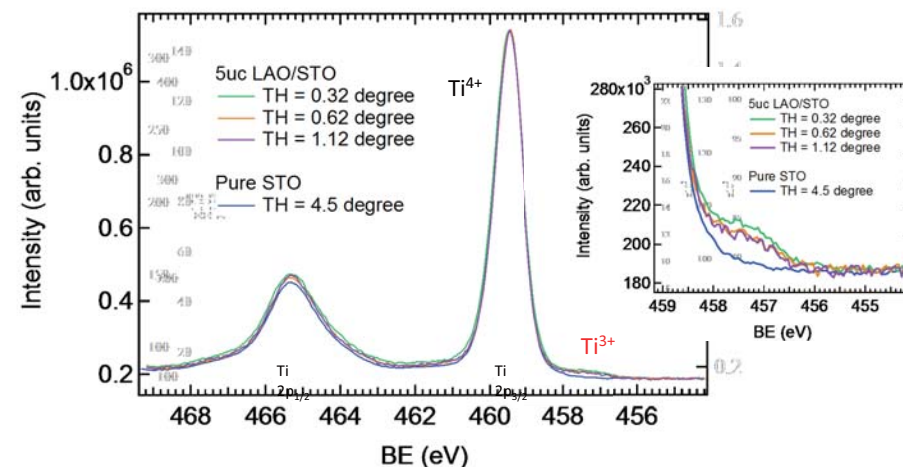
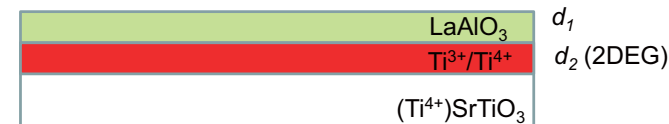
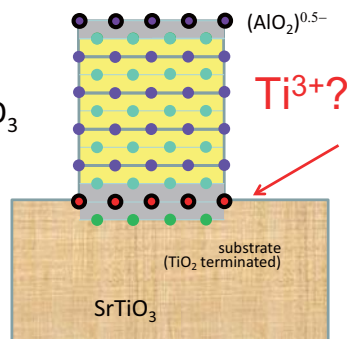
LaAlO₃/SrTiO₃ (001)



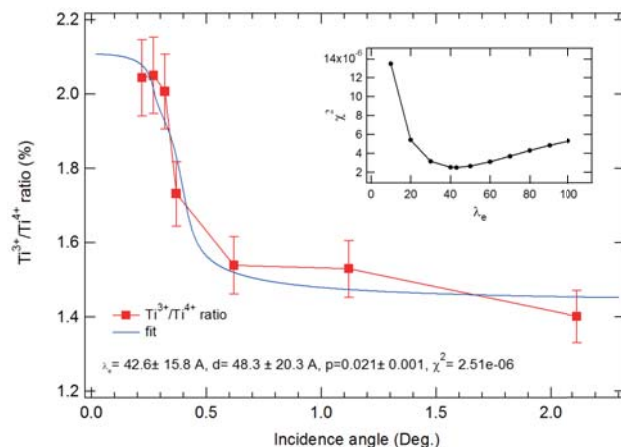
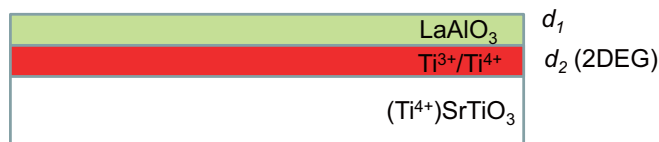
grown with PLD, 10⁻⁵ torr O₂, 850 C
annealed at 100 mtorr of O₂



5 u.c.
LaAlO₃



Measure intensity ratio Ti³⁺/Ti⁴⁺ as a function of incident angle



Chu et al., Appl. Phys. Lett. 99, 262101 (2011)

$d_2 = 48.3 \pm 20.3 \text{ \AA}$
~ 12 u.c.

$\alpha = 0.021$
(Ti³⁺/Ti⁴⁺ in d_2)

Total carriers
~ 0.24 e / 2D u.c.

Consistent with
electronic
reconstruction but
only half the amount
O vacancies?

Challenging future directions of Photoemission Spectroscopy

1. ARPES at submicron to tens of nanometer scale,
using Schwartzchild optics or zone plates.
Need brighter light sources.
2. Time-resolved PES.
Pump-probe: dynamics.
Need efficient detection and brighter sources.
lasers or laser+SR.

Thanks for your attention